

one or more of the following U.S. patents: *Li et al.*, *Hartig et al.*, *Ishii et al.*, *Ueda et al.*, *Kadomura et al.* and *Moslehi et al.*

In the Final Office Action, the Examiner states that giving the broadest reasonable interpretation of the word "peripheral" would render the claims unpatentable (Final Office Action, page 4, last paragraph). As is known to those skilled in the art, conventionally a gas shower head is used to flow gas from the top portion of the plasma processing system. Clearly, there is a distinction between a top region and a peripheral region of a plasma processing chamber. Accordingly, It is respectfully submitted that even in the broadest sense, a peripheral region of a plasma processing chamber cannot be interpreted to be a top region of the plasma processing chamber.

The Applicant reiterates the arguments made in the amendment dated January 26, 2001 and respectfully submits that the cited art does not teach or suggest controlling flow of a source gas suitable for use to etch a substrate in the plasma processing chamber into at least two different regions, including at least one peripheral region of the plasma processing chamber.

Again, it should be noted that *Moslehi et al.* does not teach or suggest gas flowing from a peripheral region of the plasma processing chamber. The gas shower head described by *Moslehi et al.* only puts gas from the top portion of the plasma processing chamber. *Hartig et al.*, similar to the teaching of *Moslehi et al.*, describes a gas shower which flows gas only from the top portion of the plasma processing chamber. Similarly, the process gas mass flow controller of *Ishii et al.* flows the source gas only from a top portion. *Li et al.* proposes injecting source gas components from ports around the peripheral of the wafer, however, it does not teach or suggest flowing the source gas into at least two different regions including at least one peripheral region of the plasma processing chamber.

In view of foregoing, it is respectfully submitted that claims 1-37 are patentably distinct from the cited references. Reconsideration of the application and an early Notice of Allowance are earnestly solicited. If there are any issues remaining which the Examiner believes could be resolved through either a Supplemental Response or an Examiner's Amendment, the Examiner is respectfully requested to contact the undersigned at the telephone number listed below. Applicants hereby petition for an extension of time which may be required to maintain the pendency of this case, and any

required fee for such extension or any further fee required in connection with the filing of this Amendment is to be charged to Deposit Account No. 50-0388.

Respectfully submitted
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